

RF Gridded Ion Sources

«TYPHOON» – Series



Industrial RF Plasma Systems



Wide application range

- Cleaning and Activation
- Ion-Beam Etching
- Ion-Assisted Deposition
- Ion-Beam Sputtering
- Ion-Beam Milling

- Built-in impedance matching network (M'Box).
- Convergent, collimated and divergent ion beam by request.
- Easy control by communication port.
- High density of ion current.
- Ion flux without contaminations.
- Long lifetime, easy maintenance.
- Full set of power supplies available including automatic controller.



Parameter	Value	Parameter	Value
Working frequency	13.56 MHz	Energy control	Remote
Matching impedance control	Automatic / Manual	RF input	7/16
Working power	300-2500 W	Input Impedance	50 Ohm
Ion Energy	150-1500 eV	Power connection	110-220 V; 50 / 60 Hz
Current density	Up to 5 mA /cm ²	Magnetic field	DC Coil
Working pressure	0.03-0.5 Pa	Cooling	Water / Fan
Type of gas	Any gases	Grid's material	Molybdenum, titanium, graphite, tantalum
Quantity of grids	2, 3		